On the photosensitive layer was coated a 3% by weight aqueous solution of polyvinyl alcohol (saponification degree: 98%, polymerization degree: 500) so as to have a dry coating weight of 2.5 g/m², and dried at 120° C for 3 minutes to form an overcoat layer layer, whereby a photosensitive lithographic printing plate was prepared.

The photosensitive lithographic printing plate was subjected to scanning exposure of solid image and dot images of from 1 to 99% (every 1%) using an FD-YAG laser (Plate Jet 4 manufactured by CSI Co., Ltd.) in an exposure amount of 100 $\mu \text{J/cm}^2$ at 4,000 dpi under condition of 175 lines/inch, and then subjected to standard processing automatic developing machine (LP-850P2 manufactured by Fuji Photo Film Co., Ltd.) provided with Developing Solution 1 shown below and a finishing gum solution (FP-2W manufactured by Fuji Photo Film Co., Ltd.). The condition of pre-heating was such that a temperature of the plate surface reached was 100°C. A temperature of the developing solution was 30°C and a period of immersion in the developing solution was about 15 seconds.

Developing Solution 1 had the composition shown below and the PH thereof was 11.5 at $25\,^{\circ}\text{C}$ and the electric conductivity thereof was 5 mS/cm.

<Composition of Developing Solution 1>

Potassium hydroxide

0.15 g

Polyoxyethylene phenyl ether (n=13) 5.0 g Chelating agent (Chilest 400) 0.1 g Water 94.75 g

EXAMPLES 2 TO 5

Each lithographic printing plate was prepared in the same manner as in Example 1 except for changing the developing solution used in Example 1 to each of the developing solutions shown in Table 1 below.

TABLE 1

School S	Example 3 Example 4	Example 5	troxide 0.2 g	(n=10)		senzoic 1 g	92.7 g	PH: 12.3	Electric conductivities
Doil 9 Poteastum hydroxide 5.0 9 Triethanolanine 0.1 9 Photastum hydroxide Polyovethylene 44.75 9 Chilest 400 Water PH: 11.9	Doil 9 Poteastum hydroxide 5.0 9 Triethanolanine 0.1 9 Photastum hydroxide Polyovethylene 44.75 9 Chilest 400 Water PH: 11.9	Exam	Potassium hyd Polyoxyethyle	phenyl ether Anon LG	Chilest 400	p-tert-Butylb	Water	PH:	Flectric
0.15 g Pot 5.0 g Trip 0.1 g Phe 44.75 g Chi	0.15 g Pot 5.0 g Trip 0.1 g Phe 44.75 g Chi	Example 4		5.0 g	0.1 g	93.4 9			witu:
0.15 g 5.0 g 0.1 g 94.75 g	Potassium Nydroxide 0.15 g Potassium Nydroxide 0.15 g Polyoysthylene (n=10) 0.1 g Chilest 400 0.1 g Water 94.75 g		Potassium hydroxide Triethanolamine	phenyl ether (n=12)	Chilest 400	Water		PH: 11.9	Electric conduct
	Example 3 Potassium hydroxide Polyoxyethylene Polyoxyethylene Chilest 400 Water PH: 11.7 Electric conducts		0.15 g 5.0 g		94.75 g				vitv:
0.15 g Potass 5.0 g Polyoo napht 0.1 g Chilee 94.75 g Water		Example 2	Potassium hydroxide Polyoxyethylene phenyl other (nel0)	Chilest 400	Water			PH: 11.8	Electric conductivity: